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## **PICOSUN PACKAGE GATHER BIG INTEREST AT ALD 2008 CONFERENCE IN BRUGES, BELGIUM**

**Otaniemi Campus, Espoo, FINLAND – July 4, 2008** – AVS ALD 2008, the 8<sup>th</sup> International Conference on Atomic Layer Deposition held in Bruges, Belgium, became a convincing step forward for Picosun Oy, the Finnish Atomic Layer Deposition (ALD) reactor manufacturer. “We registered an impressive increase in people’s interest in the Picosun Package, the combination of hardware, software, training, consulting and service solutions offered by the company,” says Juhana Kostamo, Managing Director of Picosun.

“As a direct result of our performance during the Conference, we received some three dozen extremely serious enquiries from the scientific community, research institutions and various business enterprises,” Juhana Kostamo says.

“I have often said that our strategy of building a firm foundation on first class products and first tier customers telling others of the quality of our package is going to be a formula for unprecedented success. I am happy to say that we are now seeing clear signs of this,” Mr. Kostamo says.

During the ALD conference, Picosun Oy re-introduced the inventor of the ALD method, Doctor Tuomo Suntola, to a whole new generation of ALD-enthusiasts. Picosun also successfully introduced world’s most experienced designer of ALD systems, Mr. Sven Lindfors, to the wide global ALD community. Today, Suntola is Member of the Board of Directors and Lindfors is Chief Technology Officer of Picosun.

“People at the conference were actually asking autographs from Dr Suntola and Sven Lindfors. And, indeed, they are the stars of the ALD world, dating their unique co-operation back to the earliest days of the method,” says Juhana Kostamo.

Daniel Lewis Ray, from the University of Colorado at Boulder, recently praised Dr. Suntola as the inventor of the ALD method back in 1974 in his *spotlight article* at [www.nanowerk.com](http://www.nanowerk.com), and went on to say: “Despite being invented more than three decades ago, the technique of atomic layer deposition is continuing to advance and it promises to hold the key to perhaps hundreds of future advancements. From the creation of new or more effective chemicals to the development of mechanically driven computers, everything suggests that ALD’s role in nanotechnology and nanoscience will only continue to grow.”

### **About Picosun Oy**

Picosun is an international ALD equipment manufacturer with world-wide sales and service. Picosun develops and manufactures ALD reactors for micro- and nanotechnology applications. Picosun represents continuity to over three decades of ALD reactor manufacturing in Finland. Picosun provides its customers with versatile, reliable and user-friendly ALD process tools, which offer unique scalability from research to production. Picosun is based in Espoo, Finland and has its U.S. headquarters in Detroit, Michigan. SUNALE™ ALD process tools are installed in various universities, research institutes and companies across Europe, USA and Asia. Doctor Tuomo Suntola, inventor of ALD technology is Member of the Board of Directors of Picosun. World’s most experienced ALD reactor designer Sven Lindfors is Picosun’s Chief Technology Officer and one of the founders of the company. Picosun is a part of Stephen Industries Inc Oy.

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